



PTO/SB/08A (10-01)
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Substitute for form 1449A/PTO		Complete if Known			
		Application Number	10/627,303		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)		Filing Date	7/24/03		
		First Named Inventor	Patel		
		Art Unit	Not Yet Assigned		
		Examiner Name	Not Yet Assigned		
Sheet	1	of	6	Attorney Docket Number	P109-US

U.S. PATENT DOCUMENTS					
Examiner Initials ¹	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number - Kind Code ² (if known)			
BNT		US- 3,511,727	05-12-1970	Hays, R.G.	
		US- 4,190,488	02-26-1980	Winters, H.F.	
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		US- 6,162,367	12-19-2000	Tai et al.	
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		US- 2002/0196524 A1	12-26-2002	Huibers, et al.	
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		US- 2002/0047172 A1	04-25-2002	Reid	
		US- 2003/0166342 A1	09/04/03	Chinn, et al.	

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Examiner Initials ¹	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
		Country Code ³ - Number ⁴ - Kind Code ⁵ (if known)				
BUT		EP-0704884-A2	04-03-1996	Mehta, J.		
		EP-0822582-A2	02-04-1998	Bhardwaj, J.K.		
		EP-0822584-A2	04-04-1998	Bhardwaj, J.K.		
		WO-99/49506	09-30-1999	McQuarrie, A.D.		
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		WO-98/32163	07-23-1998	Tai et al.		

Examiner Signature	Brandi Thomas	Date Considered	7/29/04
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¹ Applicant's unique citation designation number (optional). ² See Kinds Codes of USPTO Patent Documents at www.uspto.gov or MPEP 901.04. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶ Applicant is to place a check mark here if English language Translation is attached.

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Substitute for form 1449A/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)				Complete if Known	
				Application Number	10/627.303
Sheet	2	of	6	Filing Date	7/24/03
				First Named Inventor	Patel
				Art Unit	Not Yet Assigned
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				Attorney Docket Number	P109-US

U.S. PATENT DOCUMENTS					
Examiner Initials	Cite No. 1	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number - Kind Code* (if known)			
BNT		US- 6,409,876 B1	06-25-2002	McQuarrie, et al.	
		US- 6,396,619 B1	05-28-2002	Huibers, et al.	
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BNT		US- 6,197,610 B1	03/06/2001	Toda	
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		Country Code ³ - Number ⁴ - Kind Code ⁵ (if known)				
BNT		JP-1997/09251981-A	09-22-1997	Kazuaki et al.		
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		JP-1986/61053732-A	03-17-1986	Arata et al.		
		JP-1986/61134019-A	06-21-1986	Shinji et al.		
		JP-1986/61181131-A	08-13-1986	Shinji et al.		

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Sheet	4	of	6	Attorney Docket Number	P109-US

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS			
Examiner Initials [*]	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T ²
BNT		ALIEV et al., "Development of Si(100) Surface Roughness at the Initial Stage of Etching in F ₂ and XeF ₂ Gases Ellipsometric Study", Surface Science 442 (1999), pp. 206-214.	
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	6	Group Art Unit	Not Yet Assigned
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BUT		Kurt Williams, Etch Rates for Micromachining Processing-Part II, 2003 IEEE, Pgs 761-778, Journal of Microelectromechanical Systems, Vol. 12, No. 6, December 2003.	
		WINTERS et al., "The Etching of Silicon with XeF ₂ Vapor", Appl. Phys. Letter, Vol. 34(1) (January 1, 1979), pp. 70-73.	
		XACTIX, Inc., Marketing Brochure (June 27, 1999).	
		"Xenon Difluoride Isotropic Etch System: Seeing is Believing", Surface Technology Systems Ltd. brochure, Newport, UK (date unknown).	
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		First Named Inventor	Patel		
		Group Art Unit	Not Yet Assigned		
		Examiner Name	Not Yet Assigned		
Sheet	6	of	6	Attorney Docket Number	P109-US

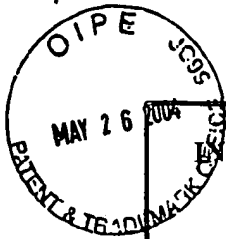
OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS			
Examiner Initials ¹	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T ²
BNT		SEBEL et al., "Reaction Layer Dynamics in Ion-Assisted Si/XeF ₂ Etching: Temperature Dependence", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 18, No. 6, (Nov. 2000), pp. 2759-2769 (abstract only).	
		SEBEL et al., "Silicon Etch Rate Enhancement by Traces of Metal", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 17, No. 3, (May/June 1999), pp. 755-762 (abstract only).	
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BNT		TODA et al., "Thin Beam Bulk Micromachining Based on RIE and Xenon Difluoride Silicon Etching", International Solid State Sensors and Actuators Conference (Transducers '97), Chicago, IL, Vol. 1 (June 16 - 19, 1997), pp. 671-674.	
		SEBEL et al., "Etching of Si Through a Thick Condensed XeF ₂ Layer", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 18, No. 5 (Sep/Oct 2000), pp. 2090-2097 (abstract only).	

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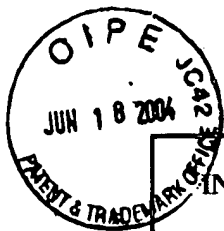
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INFORMATION DISCLOSURE CITATION PTO-1449			ATTY. DOCKET NO. P109-US		SERIAL NO. Not Yet Assigned		
			APPLICANT Patel, et al.				
			FILING DATE 7/24/03		GROUP Not Yet Assigned		
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
BNT	6,028,690	02/22/00	Carter, et al.	359	224		
FOREIGN PATENT DOCUMENTS							
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
EXAMINER	Brandi Thomas			DATE CONSIDERED 7/29/04			

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U.S. PATENT DOCUMENTS							
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BNT	6,522,454	02/18/03	Meier, et al.				
FOREIGN PATENT DOCUMENTS							
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						<input type="checkbox"/>	<input type="checkbox"/>
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
EXAMINER	<i>Brandt</i>			DATE CONSIDERED 7/29/04			

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